

2814

Atty Docket No.: 0630.0021C

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the PATENT application of:

Berry et al

Examiner: Le, Thao X.

Serial No.: 09/505,695

Group Art Unit: 2814

Filed: February 17, 2000

For: Method of Photoresist Ash Residue Removal

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TRANSMITTAL LETTER

COMMISSIONER FOR PATENTS
Washington, D.C. 20231

Sir:

Transmitted herewith for filing in the above-identified application is an Amendment
(6 pages).

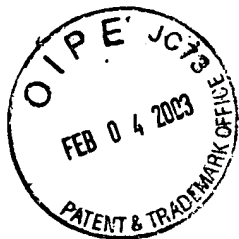
Respectfully submitted,



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February 4, 2003



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AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Responsive to the Office Action of November 18, 2002, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 7 to 11, 13, and 15 to 23. Please amend claims 2 and 14 as shown below. Please see the Appendix attached hereto for a version of the claims without markings to show the changes made.

-- 2. (Twice Amended) The method of claim 24 wherein the gas and/or vapor is

B1 comprised of at least one member selected from the group consisting of amines, alcohols, thiols, ammonia, sulfur dioxide, sulfur dioxide and oxygen, sulfur trioxide, hydrogen sulfide, carbon dioxide, carbon monoxide, carbon sulfide, carbonyl sulfide, hydrogen peroxide, and water.